

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:	)	Group Art Unit: <b>2112</b>
	)	
<b>Shinichiro Nohdo</b>	)	
	)	Confirmation No.: <b>3173</b>
Application No. <b>10/812,602</b>	)	
	)	
Filed: <b>March 30, 2004</b>	)	
	)	
For: WAFER, EXPOSURE MASK, METHOD OF	)	Examiner: <b>Rebecca Slomski</b>
DETECTING MARK AND METHOD OF	)	
EXPOSURE	)	

MAIL STOP AMENDMENT  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE TO DECEMBER 11, 2006 OFFICE ACTION**

Dear Sir:

This Amendment is submitted in response to the Office Action mailed December 11, 2006. Applicant respectfully requests amendment of the patent application, and reconsideration and allowance of the pending claims.